EXHIBIT 2

WHAT IS CLAIMED IS:

- 1. The method of depositing a film onto a substrate which comprises depositing at least one layer in the presence of at least one deposition-rate enhancing substance.
 - 2. The method of claim 1 wherein the substrate is brittle.
 - 3. The method of claim 1 wherein the substrate is transparent.
 - 4. The method of claim 1 wherein the substrate is a glass.
 - 5. The method of claim 1 wherein the substrate is a silicate glass.
- 6. The method of claim 1 wherein the layer comprises metal and silicon oxides.
- 7. The method of claim 1 wherein the layer comprises tin and silicon oxides.
- 8. The method of claim 1 wherein the layer comprises tin, silicon, and phosphorus oxides.
- 9. The method of claim 1 wherein the layer comprises silicon and boron oxides.
- 10. The method of claim 1 wherein the layer comprises tin, silicon, phosphorus and boron oxides.
- 11. The method of claim 1 having at least a first layer and a second layer.
- 12. The method of claim 11 wherein the second layer comprises a metal oxide.
- 13. The method of claim 11 wherein the second layer comprises a mixture of tin oxides and fluorine.
- 14. The method of claim 1 wherein the deposition-rate-enhancing substance is a phosphite.
- 15. The method of claim 1 wherein the deposition-rate-enhancing substance is water.

- 16. The method of claim 1 wherein the deposition-rate-enhancing substance comprises water and a phosphite.
- 17. The method of claim 1 wherein the deposition-rate-enhancing substance comprises water, a borate and a phosphite.
- 18. The method of claim 1 wherein the deposition-rate-enhancing substance is a phosphite ester.
- 19. The method of claim 1 wherein the deposition-rate-enhancing substance is triethyl phosphite.
- 20. The method of claim 1 wherein the deposition-rate-enhancing substance is trimethyl phosphite.
- 21. The method of claim 1 wherein the deposition-rate-enhancing substance comprises a mixture of triethyl and trimethyl phosphites.
- 22. The method of claim 11 comprising a plurality of layers, each layer having a separate refractive index.
- 23. The method of claim 22 wherein each layer has a concentration of silicon oxide and tin oxide different from the adjacent layer.
- 24. The method of claim 22 wherein the first layer has a refractive index which changes continuously between the substrate and the second layer.
- 25. The method of claim 22 wherein the second layer comprises a doped tin oxide.
- 26. The method of claim 22 wherein the second layer is deposited from a precursor mixture comprising MBTC and a fluorine-containing material.
- 27. The method of claim 22 wherein the first layer is deposited from a precursor mixture comprising MBTC and TEOS in the presence of triethyl phosphite.
- 28. An article of manufacture comprising a substrate having deposited thereon at least one layer comprising a film formed from a silicon-oxide precursor, a tin-oxide precursor and at least one deposition-rate enhancement material.
 - 29. The article of claim 28 wherein the substrate is transparent.

- 30. The article of claim 28 wherein the substrate is a glass.
- 31. The article of claim 28 wherein the substrate is a silicate glass.
- 32. The article of claim 28 wherein the layer comprises tin and silicon oxides.
- 33. The article of claim 28 wherein the layer comprises tin, silicon, and phosphorus oxides.
- 34. The article of claim 28 wherein the layer comprises tin, silicon, phosphorus and boron oxides.
 - 35: The article of claim 28 having a second layer.
- 36. The article of claim 52 wherein the second layer comprises a mixture of tin and silicon oxides and fluorine.
- 37. The article of claim 28 wherein the deposition-rate-enhancing substance is a phosphite.
- 38. The article of claim 28 wherein the deposition-rate-enhancing substance is water.
- 39. The article of claim 28 wherein the deposition-rate-enhancing substance comprises water and a phosphite.
- 40. The article of claim 28 wherein the deposition-rate-enhancing substance comprises water, a borate and a phosphite.
- 41. The article of claim 28 wherein the deposition-rate-enhancing substance is phosphite ester.
- 42. The article of claim 28 wherein the deposition-rate-enhancing substance is triethyl phosphite.
- 43. The article of claim 28 wherein the deposition-rate-enhancing substance is trimethyl phosphite.
- 44. The article of claim 28 wherein the deposition-rate-enhancing substance comprises a mixture of triethyl and trimethyl phosphites.
- 45. The article of claim 28 wherein the layer comprises a plurality of layers.

- 46. The article of claim 28 wherein the layer comprises a plurality of layers, each layer having a separate refractive index.
- 47. The article of claim 45 wherein the first layer comprises a plurality of layers, each layer of the plurality of layers having a concentration of silicon oxide and tin oxide different from the adjacent one of the plurality of layers.
- 48. The article of claim 45 wherein the first layer has a refractive index which changes continuously between the substrate and the second layer.
- 49. The article of claim 45 wherein the second layer comprises a doped tin oxide.
- 50. The article of claim 45 wherein the second layer is deposited from a precursor mixture comprising MBTC and a fluorine-containing material.
- 51. The article of claim 45 wherein the first layer is deposited from a precursor mixture comprising MBTC and TEOS in the presence of triethyl phosphite.